Investigation of Ni-based thermal bimaterial structure for sensor and actuator application

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\begin{abstract}
Thermal bimaterial structures made of Ni and Ni-diamond nanocomposite for sensor and actuator application are proposed, fabricated, and tested. Two deflection types of thermal bimaterial structures, including upward and downward bending types, can be easily fabricated by controlling electroplating sequence of Ni and Ni-diamond nanocomposite. According to thermal performance measurement, the tip deflection of upward and downward types can reach about 82.5 μm and \(-22.5 \mu m\) for a temperature change of 200 °C, respectively. In the condition, the thermomechanical sensitivity and output force are 412.5 nm/K and 97.0 μN for upward type thermal bimaterial structure; and \(-112.5 \text{ nm/K and } -26.5 \mu N\) for downward type one. Due to the low electroplating process temperature (\(-50 \degree C\)) for both Ni-based layers, diminutive pre-deformation of as-fabricated structure and strong interlaminar bonding strength are verified by SEM and vibrational test. The resonant frequency of the structure remains unchanged after 10\textsuperscript{10} cycles.
\end{abstract}

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1. Introduction

Bimaterial structure can provide thermally bended deformation due to the coefficient of thermal expansion (CTE) mismatch between two bonded materials, so-called bimorph effect \[1,2\]. Upon this effect, the bimaterial structure-based transducers can detect external stimulus of temperature change and provide temperature-driven output force simultaneously. To date, thermal bimaterial structure has been widely utilized in several microelectro-mechanical systems (MEMS) devices, such as thermal sensor \[3\], stress sensor \[4\], biological sensor \[5\], microvalve \[6\], pumping membrane \[7\], tilting micromirror \[8\], microrelay \[9\], microswitch \[10\], etc. Nevertheless, thermal bimaterial structure typically will exhibit initial deformation once the structure is released. This deformation is resulted by the residual thermal stress \[11–13\] induced in structural fabrication where structural materials have different CTE and process temperatures. Delaminating is also a common issue that may happen on the interlamination through large residual stress and low cohesive energy \[14,15\] to reduce the lifetime and reliability of thermal bimaterial structure. For a bimaterial structure, by arranging the low-CTE layer on top, thermal upward actuation can be achieved \[16,17\]. However, since metal usually has higher CTE comparing to nonmetal material, thermal upward actuation is difficult to achieve when the metal layer is deposited above the nonmetal layer \[8–10,13\]. Thus, further investigations in terms of material and process selection and structure design are still required for future applications of thermal bimaterial structure.

In recent researches, Teh et al. found that the incorporation of nano-diamonds in electrolytic Ni matrix to form Ni-diamond nanocomposite could reduce the film residual stress and render the film more compressively \[18\]. Besides, the nanocomposite could exhibit a higher CTE than that of electroplated Ni \[19\]. Therefore, this study will investigate the bimorph effect of Ni/Ni-diamond nanocomposite bimaterial and propose a newly thermal bimaterial microactuator by employing the advantages of Ni-diamond nanocomposite. It is our belief that the proposed thermal device using the Ni/Ni-diamond nanocomposite bimaterial would have better interfacial bonding strength and smaller residual thermal stress since Ni and Ni-diamond nanocomposite have different CTE but similar crystal structure and process temperature. By controlling plating sequence of Ni and Ni-diamond nanocomposite, the fabricated thermal bimaterial structure desired to have upward or downward bended deformation can also be easily achieved.

2. Bimaterial structure design

Fig. 1 shows the scheme of thermal bimaterial structures made of Ni/Ni-diamond nanocomposite bimaterial including upward and downward deflection types for bimorph effect investigation. Upon
the plating sequence of Ni and Ni-diamond nanocomposite, two deflection types of thermal bimaterial structures, including upward and downward types, are available. The designed length $L$ of fabricated thermal bimaterial structure ranged from 200 $\mu$m to 1500 $\mu$m where the width $w$ is fixed at 50 $\mu$m. The connecting beam is 50 $\mu$m long ($L_c$) and 30 $\mu$m wide ($w_c$). The thickness of Ni and Ni-diamond nanocomposite layers are determined according to the optimum thermomechanical sensitivity $S_T$ defined as tip deflection $d$ for a temperature change $\Delta T$:

$$S_T = \frac{d}{\Delta T}$$  \hspace{1cm} (1)

where $d$ and following $F$ are the thermally generated tip deflection and the output force of a thermal bimaterial structure, respectively. The deflection and force can be expressed by the following equations [1]:

$$d = \frac{3w_1w_2E_1E_2t_1t_2(t_1 + t_2)(\alpha_1 - \alpha_2)}{(w_1E_1t_1^2)^2 + (w_2E_2t_2^2)^2 + 2w_1w_2E_1E_2t_1t_2(2t_1^2 + 3t_1t_2 + 2t_2^2)}$$ \hspace{1cm} (2)

and

$$F = \frac{3E_1d}{L^3} = Kd$$ \hspace{1cm} (3)

where $E_i$, $\alpha_i$, $w_i$, and $t_i$ ($i = 1, 2$) are, respectively, Young’s modulus, CTE, width, and thickness of each layer; $L$, $E$, and $K$ are, respectively, the length, flexural rigidity and spring constant of thermal bimaterial structure, and $\Delta T$ is the temperature change.

A folded structure design is introduced into the thermal bimaterial structure to increase output force and to decrease the thermal vibrational noise. For thermal bimaterial structure, the amount of thermomechanical sensitivity can be designed as high as 640.2 nm/K with the flexural rigidity of 6.61 $\times$ $10^9$ Nm$^2$, and the output force of 150.5 $\mu$N as $\Delta T = 200^\circ$C. Similarly, for downward type thermal bimaterial structure, the layer thickness of Ni and Ni-diamond nanocomposite are also determined to be 3 $\mu$m and 6 $\mu$m, respectively.

3. Fabrication

Fig. 3 depicts the fabrication process of the proposed thermal bimaterial structure. Initially, the 0.5 $\mu$m thick SiO$_2$ on a silicon wafer with patterned etching windows is first coated with 5 $\mu$m thick AZP-4620 photoresist (PR) and patterned as sacrificial layer (Fig. 3(a)). After hard baking, it is followed by sputtering seed layer of 1000 $\AA$ Cu onto 200 $\AA$ Ti as adhesion layer. 15 $\mu$m thick AZP-4620 PR is then spin coated and patterned to form the plating mold of thermal bimaterial structure, as shown in Fig. 3(b). For upward type thermal bimaterial structure, the 6 $\mu$m thick composite-plating of Ni-diamond layer is deposited first to construct the bottom layer of thermal bimaterial structure. Subsequently, 3 $\mu$m thick electroplated Ni is deposited to construct the top layer (Fig. 3(c)). Table 1 shows the plating bath condition, and the plating temperatures of both layers are kept at 50 $^\circ$C. For the composite-plating of Ni-
diamond nanocomposite which is different from electroplated Ni, the nano-diamond particles with 350 nm in average diameter are added into a sulfuric-based Ni plating bath for the co-deposition, and the concentration of the nano-diamond particles in plating bath is 2 g/L. Finally, the fabricated thermal bimaterial structure is released after stripping the sacrificial layer by acetone solution (Fig. 3(d)), and the silicon underneath is removed by KOH solution (Fig. 3(e)). For downward type thermal bimaterial structure, the fabrication process is similar to the upward one except switching the plating sequence of Ni-diamond nanocomposite and Ni in Fig. 3(c). By controlling plating sequence of Ni and Ni-diamond nanocomposite, two deflection types of thermal bimaterial structures including upward and downward are easily fabricated.

Fig. 4(a) and (b) shows the scanning electron microscope (SEM) pictures of the upward and downward types of fabricated thermal bimaterial structures. It is found that no initial deformation is observed as proposed due to the same low process temperature of electrodeposited Ni and Ni-diamond nanocomposite for lower residual thermal stress in thermal bimaterial structure.

Table 1

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<tr>
<th>Plating bath conditions of Ni and Ni-diamond nanocomposite for structural layers of thermal bimaterial structure.</th>
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Fig. 3. Fabrication process of thermal bimaterial structure: (a) 5 μm AZP-4620 PR deposition and patterning; (b) sputtered Ti/Cu as an adhesion and seed layer, then 15 μm AZP-4620 PR deposition and patterning as the plating mold structure; (c) layers electroplating: Ni-diamond nanocomposite for bottom layer, and Ni for top layer (i.e. upward type); (d) structure releasing; (e) silicon removing by KOH.

Fig. 4(a) and (b) shows the scanning electron microscope (SEM) pictures of the upward and downward types of fabricated thermal bimaterial structures. It is found that no initial deformation is observed as proposed due to the same low process temperature of electrodeposited Ni and Ni-diamond nanocomposite for lower residual thermal stress in thermal bimaterial structure.
Fig. 4. SEM pictures of fabricated thermal bimaterial structures: (a) upward type: Ni layer on top of Ni-diamond nanocomposite layer; (b) downward type: Ni-diamond nanocomposite layer on top of Ni layer.

Fig. 5. Schematic diagram of set-up for thermal performance measurement of thermal bimaterial structure.

Fig. 6. Thermal performance measurement results and fitting curves in terms of the tip deflection of thermal bimaterial structure at elevated temperature: (a) upward type; (b) downward type.

Measuring the focus variation ($\Delta Z$) and the measurement accuracy of $\Delta Z$ is about 0.5 $\mu$m on positional $z$-adjustment. The measured out-of-plane tip deflections of fabricated thermal bimaterial structures including upward and downward types with length of 800 $\mu$m, 1000 $\mu$m, and 1500 $\mu$m are observed with temperature change from 0 $^\circ$C to 200 $^\circ$C. The relationship between tip deflection and elevated temperature is plotted in Fig. 6(a) and (b). According to the measured results of thermal performance, as structure length $L = 1500$ $\mu$m and temperature change $\Delta T = 200$ $^\circ$C, the measured tip displacement of upward and downward types can reach around 82.5 $\mu$m and $-22.5$ $\mu$m, respectively. In this condition, the thermomechanical sensitivity and output force are calculated, respectively, to be 412.5 nm/K and 97.0 $\mu$N for upward type thermal bimaterial structure; and $-112.5$ nm/K and $-26.5$ $\mu$N for downward type one.

From above calculated results of upward type thermal bimaterial structure, the thermomechanical sensitivity and output force are smaller than the theoretical calculation; and the thermal performance in tip deflection of downward type is not as large as upward type. It seems that the CTE difference between Ni and Ni-diamond nanocomposite in the thermal bimaterial structure is not equal to the cantilevers’ that made of single material layer. Assuming material properties of bottom structural layers of thermal bimaterial structure are the same as cantilever’s that made of single Ni or Ni-diamond nanocomposite layer. Using Eq. (2) and the measured data of Fig. 6(a) and (b), the CTE of the top structural layer of thermal bimaterial structure have been modified to fit the experiment data. Therefore, the CTE of top structural layer of Ni in upward type is modified to be $16.9 \times 10^{-6}$/C which is 8.3% deviation from single Ni cantilever. Similarly, the CTE of top structural layer of Ni-diamond nanocomposite in downward type is modified to be $16.2 \times 10^{-6}$/C which is 16.5% deviation from single Ni-diamond nanocomposite cantilever.

Seed layer effect may be the major cause resulting in the aforementioned CTE variation. While Ni-diamond nanocomposite is
used as the top structural layer of thermal bimaterial structure in downward type, the plating seed layer of Ni-diamond nanocomposite is a 3 µm thick electroplated Ni. On the contrary, as Ni-diamond nanocomposite is used as the bottom structural layer in upward type, the plating seed layer is 1000 Å sputtering Cu which is similar to single material cantilever. According to atomic force microscope (AFM) surface images of 6 µm Ni-diamond nanocomposite on 3 µm electroplated Ni and 1000 Å sputtered Cu seed layers as shown in Fig. 7(a) and (b), respectively, the Ni-diamond nanocomposite electroplated on the Ni layer has a higher surface roughness value ($R_a$) than that on the sputtering Cu layer. The rougher surface could be attributed to that grain structure difference of Ni-diamond nanocomposite that may vary with the different seed layers and so does the material property of CTE. Further material characterization is required for verification.

### 4.2. Interlaminar reliability test

Fig. 8(a) and (b) shows the side wall SEM pictures of two bimaterial structure types including upward and downward, respectively. Due to similar crystal structures of Ni-base between plating Ni and Ni-diamond nanocomposite, the outside interlaminar boundary of fabricated thermal bimaterial structure is not evident. Fig. 9 also shows the bright field transmission electron microscope (TEM) image of cross section of fabricated thermal bimaterial structure that the interface boundary displays strong bonding as similar Ni crystal structure. To further investigate the bonding strength, the following vibration test [22] is performed.

A chip with the thermal bimaterial structure is placed and fixed on piezoelectric shaker which is controlled by waveform generator connected to MEMS motion analyzer (MMA G2TM, Etec). The thermal bimaterial structure is driven by an external piezoelectric shaker at destructive resonant frequency of the 5th vibration mode (the first torsion shape) obtained from the modal analysis by the commercial finite-element-analysis (FEA) software ANSYS. For the upward type with 1000 µm length, the 5th resonant frequency is about 108.2 kHz with 0.90 ± 0.05 µm amplitude monitored by an interferometer connected to MMA. Because the delaminated interface has higher influence on the decrement of the resonant frequency of higher order modes, the shift in resonant frequency of the 5th vibration mode is detected to investigate the delamination between interlaminar layers of thermal bimaterial structure. The vibration test result is plotted in Fig. 10 that the resonant frequency is found to be unchanged during 10⁹ cycles of continuous vibration. In general, the infinite life of material is defined as no failure happened after 10⁶–10⁷ cycles in fatigue test [23]. In this study, the test is only performed up to 10⁹ cycles, and the measured resonant frequency remains unchanged after 10⁹ cycles. This result shows good interlaminar bonding ability between electrodeposited Ni and Ni-diamond nanocomposite since two materials in the thermal bimaterial structure are Ni based.
4.3. Electro-thermal driven discussion

If the aforementioned bimaterial structures will be used for microactuation application, several design issues should be addressed. In general, electro-thermal microactuators are driven by electric heating, the driving energy $Q$ and the generating temperature change $\Delta T$ can be expressed as follows:

$$Q = \frac{V^2}{R} \Delta t = mC \Delta T$$  \hspace{1cm} (5)

and

$$\Delta T = \frac{V^2 \Delta t}{R \cdot mC} = \frac{V^2 \Delta t}{\rho (L/A) \cdot c \cdot D} = \frac{V^2 \Delta t}{\rho D C L^2}$$  \hspace{1cm} (6)

where $V$, $R$, $\Delta t$, $m$, $L$, and $A$ are, respectively, driving voltage, electrical resistance, heating time, mass, total length and cross-sectional area of electro-thermal microactuator. $\rho$, $D$, and $C$ are electrical resistivity, density, and specific heat of structural material, respectively. Therefore, while supply voltage is applied to the bimaterial structure, the layer with lower electrical resistivity, i.e. pure Ni layer ($1.59 \times 10^{-5} \Omega \text{cm}$, as measured by four-point probe), will have larger temperature change than that of Ni-diamond nanocomposite ($1.87 \times 10^{-5} \Omega \text{cm}$, as measured). Since the CTE of Ni is smaller than that of Ni-diamond nanocomposite, the different temperature change to each structural layer will affect the thermal performance in terms of tip deflection due to the neutralization of the thermal elongations of Ni and Ni-diamond nanocomposite. Similarly, this problem also happens to the bimaterial structure of metal/p+Si while it is utilized as an electro-thermal microactuator [2,10,13,24]. In order to prevent the occurrence of neutralization, an insulated layer, such as oxide and nitride, is generally used to assure only one heating layer. However, the insulated layer may cause the delamination in the thermal bimaterial structure to reduce the lifetime and reliability of microactuator as mentioned before.

Although the neutralization is unavoidable in the Ni/Ni-diamond nanocomposite bimaterial structure without having an insulated layer in between, it could be solved further by controlling the driving voltage and concentration of Ni-diamond nanocomposite to keep both layers have the same temperature change, i.e. $\Delta T_{Ni-d}=\Delta T_{Ni}$ during electric heating. From Eq. (6), as $\Delta T_{Ni-d}=\Delta T_{Ni}$, it can be found that $\rho_{Ni-d}d_{Ni-d}c_{Ni-d}=\rho_{Ni}d_{Ni}c_{Ni}$. According to the rule of mixture [25], the incorporation of diamond will result in the increase of Ni electrical resistivity and the decrease of Ni density simultaneously. By well controlling the total amount of incorporated nano-diamonds, the multiple of electrical resistivity, density, and heat capacity can be the same to both materials. Thus, the correlation between material properties and nano-diamond concentration requires further investigation for optimal microactuation using the Ni/Ni-diamond bimaterial structure.

5. Conclusions

Thermal bimaterial structures made of electrodeposited Ni and Ni-diamond nanocomposite for CTE mismatch are fabricated successfully to achieve upward and downward out-of-plane displacement easily by controlling plating sequence of electrodeposited Ni and Ni-diamond nanocomposite. Due to the same low process temperature (~50°C) of electrodeposited Ni and Ni-diamond nanocomposite, the residual thermal stress and initial deformation of fabricated thermal bimaterial structures are small. Since two materials in the thermal bimaterial structure are Ni based, the fabricated thermal bimaterial structure also shows good interlaminar bonding ability between electrodeposited Ni and Ni-diamond nanocomposite. In addition, electrodeposited Ni and Ni-diamond nanocomposite are compatible with MEMS and CMOS fabrication technologies via a one-step, selective on-chip deposition process at low temperatures (~50–90°C). Therefore, thermal bimaterial structure made of electrodeposited Ni and Ni-diamond nanocomposite can be integrated into MEMS and CMOS fabrication process for sensor and actuator application.

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References


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